<u>To:</u>

Notification about change of WCSP products' UBM process (Urgent)

TOSHIBA

Issue No. H440-3A-001P Date of issue: January 25, 2023

Quality Assurance Department Himeji Operations - Semiconductor **Toshiba Electronic Devices & Storage Corporation**

1. Outline of change

1) Background of change

Our outsourced company has informed us that an indirect material (chemical solution A) used for the UBM process in which a metallic film is formed under solder bumps will be discontinued regarding WCSP products currently being manufactured.

Due to this, we will change to a UBM process using chemical solution B with which the outsourced company has a track record of manufacturing other devices.

In order to maintain a stable supply, the names of the products after the change will not change, and a "running change" will be applied after the existing products are out of stock.

We apologize for this short notice, but we would sincerely appreciate your understanding.

2) Description of change

Product Group	MOSFET	Load Switch IC	Package Image	
Package Name	WCSP6C	WCSP4C WCSP6C		
Product Before Change	UI	BM: Ti/NiV/Cu	۲	
Product After Change	U	BM: Ti/Cu/Cu	WCSP4C WCSP6C	

X Although the chemical will be changed, the outsourced company has a track record of manufacturing other devices with the process using chemical solution B.

3) Time of change

Products after the change will be able to be mass-produced from November 2023. The products after the change will be supplied after the existing products are out of stock.

4) Products subject to change

This process change will not entail any change of the products' names. Please see the attachment.

2. Schedule for supplying products after change

The schedule for supplying products before and after the change is as follows.

Since the process after the change has a solid track record, products manufactured in the new process will be supplied after the existing products are out of stock.

We will report results of evaluating products of the new process around the end of May.

ltem	2023								2024							
	Jan.	Feb.	Mar.	Apr.	May	Jun.	Jul.	Aug.	Sep.	Oct.	Nov.	Dec.	Jan.	Feb.	Mar.	Apr.
Status of production (Old/new processes)										produc old pr		proces Runnin proces the exi The ne	art of production with new ocess unning change: Products with the ocess changed will be supplied after e existing products are out of stock the new process can be identified by e lot number.		l after \ stock.	
Announce- ment of change, notification of first lot		Anno	uncem	ent	•	Com	pletio	n of e	aluati	ons			tart of ot after		ng of th ange	e first

Changes in **5M1E** are shown below.

5M1E	Change Point
Man	No change
Machine	To be changed
Measurement	No change
Method	No change
Material	To be changed: UBM (Chemical solution $A \Rightarrow B$, Ti/NiV/Cu \Rightarrow Ti/Cu/Cu)
Environment	No change

These changes will not affect the products' electrical characteristics, reliability, etc.

4. Change points and evaluations (DRBFM)

The DRBFM is as follows.

No	Part & product/Change and its purpose		Function	Concern from change (Failure mode)	Case where a concern arises		ltem reflected (Removal of concerns)	Action (based on result of DRBFM): What action was taken?												
		Ban against change without purpose		Loss of function, lack of merchantability, and side effect	Cause, factor	Effects on customer	(Current process	Item to be reflected on	on		Item to be reflected									
	Part, product	Change	performance	caused by change		control/design		design drawing	ltem	Test result (Defectives / quantity tested)	(Measure)									
1	Machine	UBM machine	UBM forming	Decrease in characteristics yields due to deterioration of UBM's finished condition	Insufficiency in optimization of process conditions	None	- Use of proven machine - Preparation and maintenance of standard documents	None	Check on assembly yields and appearance yields		- CP control - Check in testing process									
2	UBM Cu plating	UBM Cu plating forming	UBM forming	Decrease in characteristics yields (Ron) due to failure in Cu plating	Insufficiency in optimization of Cu plating process conditions	None	Application of proven machine and process conditions	None	- Check on characteristics yields - Check on initial characteristics	Target completion date of evaluations: May 2023	- CP control - Check in testing process									
3					r c -	Decrease in characteristics yields and reliability (moisture resistance) due to degradation of UBM's finished condition	Insufficiency in optimization of mask size and etching conditions	None	Application of proven process conditions	None	- Check on characteristics yields - Reliability (THB) check		Check in testing process							
4														Decrease in characteristics yields due to deterioration of contact resistance	Thicker UBM film	None	Application of proven process conditions	None	- Check on characteristics yields - Check on initial characteristics	
5				Decrease in ball shear strength	Insufficiency in optimization of UBM structure	- Failure in device mounting - Deterioration of reliability	Application of proven process conditions	None	- Check on ball shear strength	Unit evaluations revealed no problem (0/250pcs).	CP control (Ball shear test)									
6	Metallization material				Decrease in appearance yields due to failure in product height	- Insufficiency in optimization of UBM structure - Insufficiency in optimization of mask size	None	Application of proven process conditions	None	- Check on appearance yields - Measurement of product height	Unit evaluations revealed no OK problem (0/500pcs).	CP control (Ball height measurement)								
7				Decrease in appearance yields due to failure in ball height	- Insufficiency in optimization of UBM structure - Insufficiency in optimization of mask size	None	Application of proven process conditions	None	- Check on appearance yields - Measurement of ball height	Unit evaluations revealed no OK problem (0/500pcs).	CP control (Ball height measurement)									
8				Decrease in appearance yields due to failure in ball diameter	- Insufficiency in optimization of UBM structure - Insufficiency in optimization of mask size	None	Application of proven process conditions	None	- Check on appearance yields - Measurement of ball diameter	Unit evaluations revealed no problem (0/500pcs).	CP control (Appearance inspection)									

5. Change points

The only point that will be changed in this process change will be the UBM structure.

ltem	Product Before Change	Product After Change					
Chip	No change						
Chemical Solution	Chemical solution A Chemical solution B						
UBM	Ti/NiV/Cu	Ti/Cu/Cu					
Ball Diameter/Material	No change						
Cross-sectional Structure	UBM	Solder ball					

The following are the results of unit evaluations of products from the UBM process using chemical solution B which has a track record of manufacturing. No problems were found in process capability of each item.

Unit evaluations (One representative lot)

ltem	Purpose of evaluation	Product before change	Product after change
Ball shear	UBM structure evaluation	1.86	2.33
Bal height	Product evaluation	3.01	5.90
Ball diameter	Product evaluation	2.71	4.53

7. Control plan

QC process flow (Applicable to all WCSP products subject to the change)

The basic QCS will not be affected by the process change.

Manufact	ure Production	Items Controlled/Inspected	Check Frequency		
Flow Chart	Process	items Controlled/Inspected	Check Frequency		
Ŷ	(Wafer)				
ϕ	Passivation Deposition	Film Thickness	Once / Day		
ϕ	Solde Ball UBM Deposition	Film Thickness	Once / Lot		
ϕ	Lapping	Wafer Thickness	Once / Lot		
∲□	Marking	Appearance	Once / Lot		
ϕ	Solde Ball Deposition	Ball Heigth	Once / Lot		
r h	Testing	Electrical Characteristics			
∲ –□	Dicing	Kerf Width	Once / Lot		
∇	(Taping Material) Taping				
r h	Appearance Inspection				
∇	(Packing Material) Packing				
	Quality Monitoring	Electrical Characteristics Reliability Test			
\downarrow	Shipping				
Symbol			: Sampling inspection		

The above process may be changed or rationalized based on the result in our process.

8. Construction drawing

Index

There are no differences in construction drawing before and after the process change.



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